

A petition for a three-month extension of time accompanies this response, making the response due on or before January 16, 2004. Accordingly, this reply is being timely submitted. A notice of appeal also accompanies this response.

Please amend the present application as follows:

**Amendments to the Specification**

On page 21, line 20, please change “methd” to “method”:

In a first embodiment, the opaque layer is formed by photolithography. The ~~methd~~ method comprises providing a support having microlenses and, optionally, a diffuser. In a second step, a positive-going photosensitive resin is deposited on the support after previously incorporating therein particles to make it opaque. In the case of a black coloured opaque layer for colour projection applications, carbon, ferrite black, or cobalt oxide particles can be used. A photosensitive resin can for example be the AT type resin available from the Shipley company.